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JPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Koji NOZAKI et al.**

Group Art Unit: 1752

Application Number: **10/623,679**

Examiner: **Amanda C. Walke**

Filed: **July 22, 2003**

Confirmation Number: **5083**

For: **RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN
AND PROCESS FOR FORMING THE SAME, AND
SEMICONDUCTOR DEVICE AND PROCESS FOR
MANUFACTURING THE SAME**

Attorney Docket Number: **030891**

Customer Number: **38834**

AMENDMENT AFTER FINAL

MAILSTOP: AF

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

October 10, 2006

Sir:

This paper is filed in response to the Office Action dated July 10, 2006.

Amendments to the Claims are reflected in the listing of claims that begins on page 2 of
this paper.

Remarks begin on page 11 of this paper.

Do Not Enter

Amanda C Walke 10/24/06
**AMANDA WALKER
PRIMARY EXAMINER**